

FORCE 300™

Photoresist Coater

COAT ■ DEVELOP ■ BAKE ■ WEE

A system designed and built to meet the unique requirements of the BEOL process engineer and fab manager at the lowest possible cost of ownership

Built specifically to be used in BEOL processing, the Force 300™ BEOL Model #200-300 provides users with benefits that are simply not found in any other tool at a remarkably low cost of ownership.

- Interchange operation 200 and 300 MM wafers, the user simply positions the FOUP, FOSB or Cassette, and runs the tool
- Up to 4 photoresist dispenses standard
- Top and bottom side EBR, plus bowl rinse
- Unique EBR dispense method to substantially shorten EBR process times for thicker photoresist films
- Unique Hot Plate module eliminates problems of oven contamination because of solvent/resist vapor condensate
- Hot plates no longer require regular cleaning of bake chamber
- Granular system architecture permits balanced throughput in minimum footprint in an easily expandable format
- Servo driven dispense arms permit edge to center resist dispense during chuck acceleration, reducing photoresist consumption to a virtually irreducible minimum

System Specification Overview

- Spin Speed 0 to 5000 rpm / Acceleration up to 10,000 rpm/second
- Top and bottom side EBR, concentric within $\pm .1$ mm
- 3 Hot Plate modules up to 250 C, programmable in $.1$ °C increments, uniformity $\pm 1\%$
- 1 Chill Plate module minimum 17C, programmable in $.1$ °C increments, uniformity ± 1 °C
- Class 1 environment within cabinet
- Footprint 45" Wide x 58" Deep x 84" High



Force 300™

- Small Footprint
- Automatic Load / Unload
- PC Based (Windows)
- Color LCD Touchscreen
- Extensive Process Storage Capabilities
- Brushless DC Servo Spin Motor
- Ultra High Reliability

S-CUBED

Solid • Smart • Stable

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